

Docket No. 50184

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANT: Mori et al.

SERIAL NO.: 08/726,613

FILED: October 7, 1996

FOR: DYED PHOTORESISTS AND METHODS AND ARTICLES OF
MANUFACTURE COMPRISING SAME



GROUP: 1752

EXAMINER: J. CHU

13/10/99

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THE HONORABLE COMMISSIONER OF PATENTS AND TRADEMARKS
WASHINGTON, DC 20231

SIR:

AMENDMENT AFTER FINAL REJECTION

Applicants are in receipt of the Final Office Action dated July 7, 1999 of the above-identified application. Please amend the application as follows.

IN THE CLAIMS

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50. (amended) A method for forming a photoresist relief image comprising:
applying a coating layer of a photoresist composition on an integrated circuit substrate or a liquid crystal display substrate, the photoresist composition comprising a resin binder, a photoactive component and a polymeric dye that contains one or more polycyclic chromophores, said dye compound being a polymer wherein the polymer has a weight average molecular weight of at least about 5,000; and
exposing and developing the photoresist composition coating layer to provide a photoresist relief image.

Please add the following new claims.

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60. A method for forming a photoresist relief image comprising:

applying a coating layer of a photoresist composition on a substrate, the photoresist composition comprising a photoactive component and a dye compound that comprises an

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